

comparing the quantified value of the additive with a given predetermined concentration of the additive; and

adding a solution including the additive to the plating liquid based on the compared result.

6. (Amended) A method of managing a plating liquid composition according to claim 5, further comprising removing ionic components from the plating liquid before the additive is quantified.

Kindly add the following new claims 7-9.

7. (New) A method of managing a plating liquid composition according to claim 5, further comprising:

separating and quantifying each of a plurality of additives in the sampled plating liquid using liquid chromatography by detecting the intensity of light scattered by an unevaporated solute of each additive remaining after the sampled plating liquid has been evaporated through spraying;

comparing the quantified value of each of the additives with a given predetermined concentration of each of the additives; and

adding solutions including the additives to the plating liquid based on the compared result for each of the additives.

8. (New) A method of managing a plating liquid composition according to claim 5, wherein said detecting the intensity of light scattered by the unevaporated solute includes using at least one of ultraviolet absorption and differential refraction.

9. (New) A method of managing a plating liquid composition according to claim 8, wherein said detecting the intensity of light scattered by the unevaporated solute includes using both said ultraviolet absorption and said differential refraction.
